

Status of the CMOS Strip Detector Project in Freiburg

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What is CMOS?

- Complementary **m**etal-**o**xide-**s**emiconductor
- combine n- and p-MOSFETs on one substrate
→ circuits integrated in substrate
- used in computers, phones, cameras, ...

- many vendors, established industry production lines, fast, cheap and bulk production capabilities



Why CMOS?

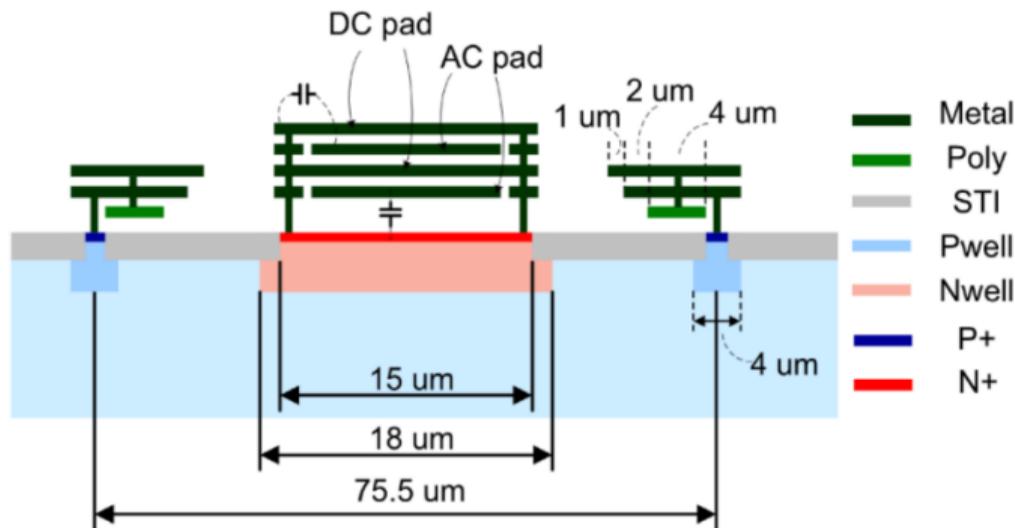
- current and future colliders rely on silicon detectors
- need to cover big areas and be radiation hard
- large areas limits us to microelectronics foundries
- only few vendors meet requirements

→ silicon is and will be a big cost driver



Passive CMOS Strip Sensors

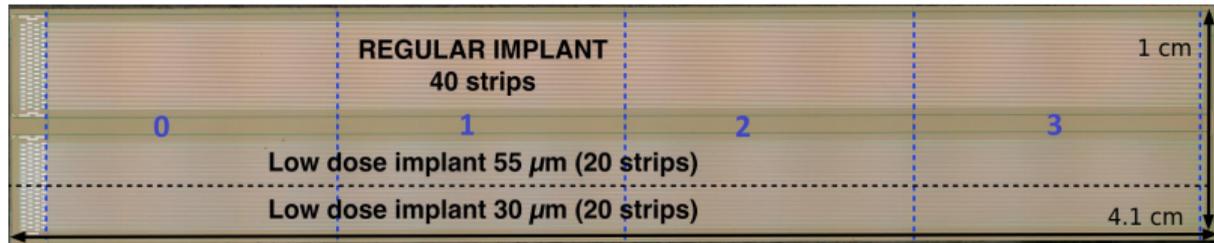
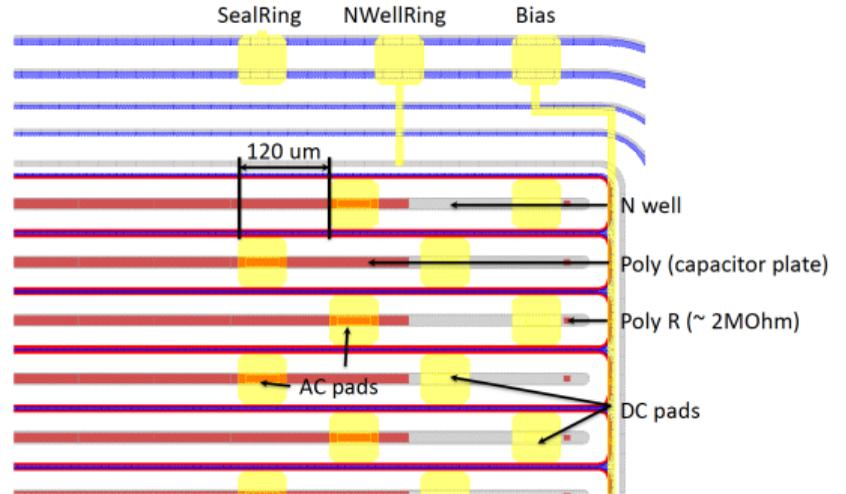
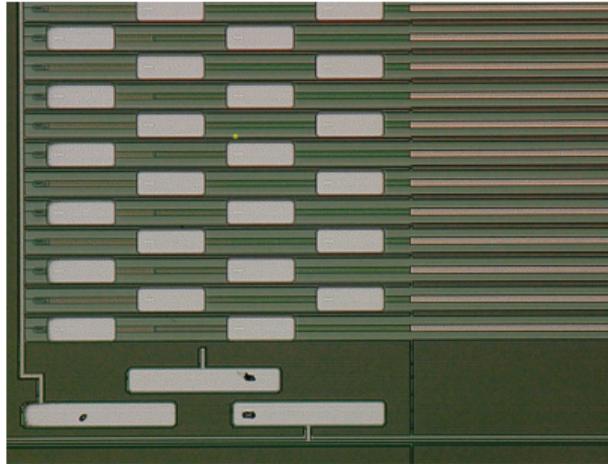
- L-Foundry 150 nm process
- float-zone silicon,
3-5 k Ω cm resistivity
- (150 \pm 10) μ m thickness
- 40 strips with 75.5 μ m pitch
- 4.1 \times 1 cm² or 2.1 \times 1 cm²
- 3 designs on one unit:
regular & low dose 30/55



- frontside processing: reticle stitching with 1 cm² masks for larger areas
- backside processing: 2nd batch has additional metal and p⁺ layer

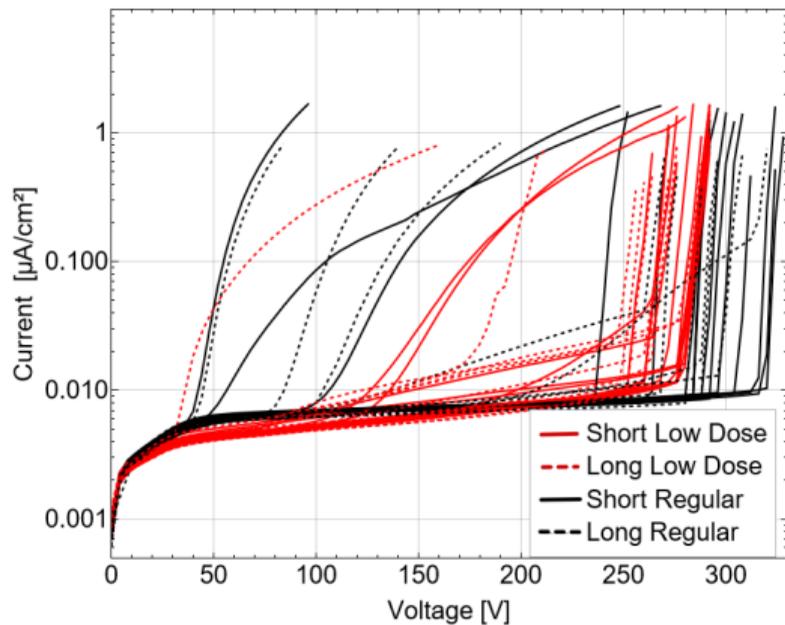


Sensor Design



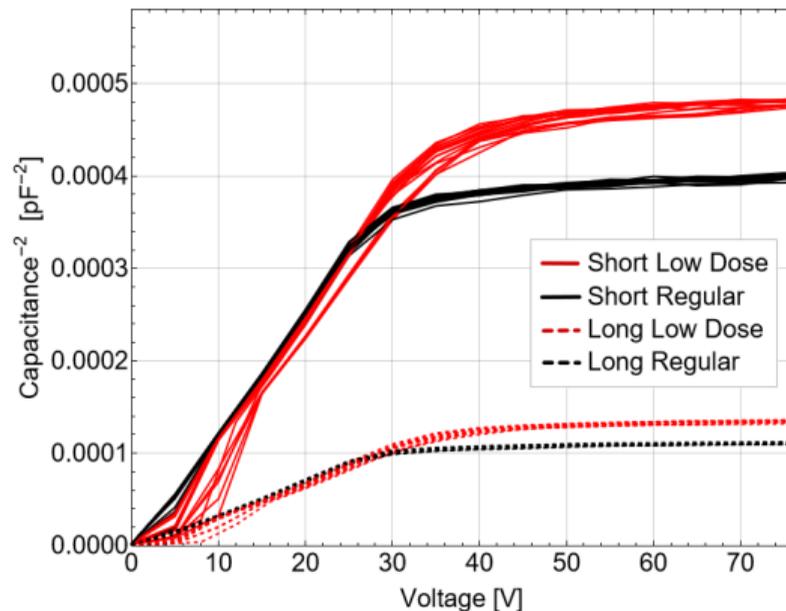
IV & CV measurements

IV



- breakdown at ~ 250 V
- full depletion at ~ 30 V
- second batch improved over first batch

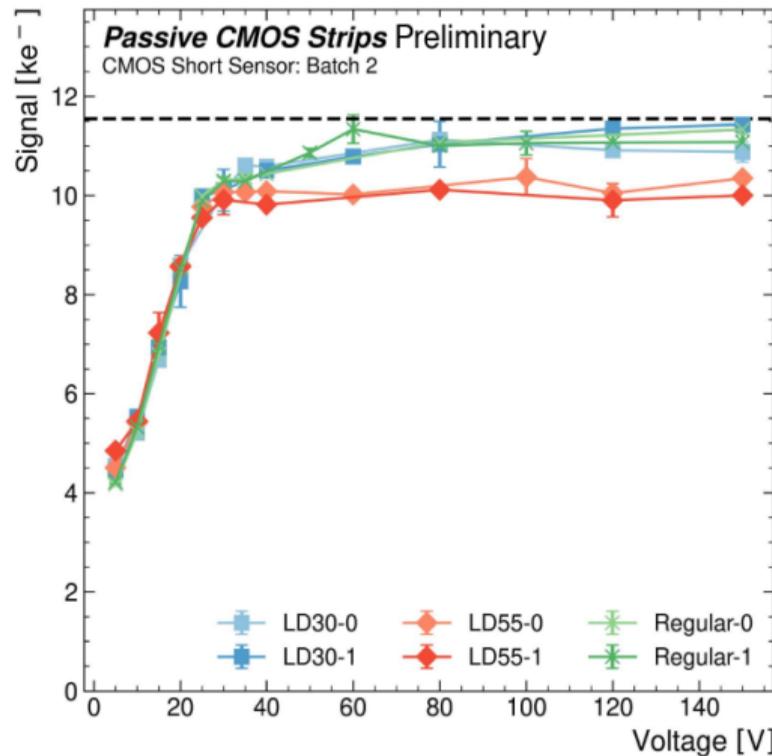
CV



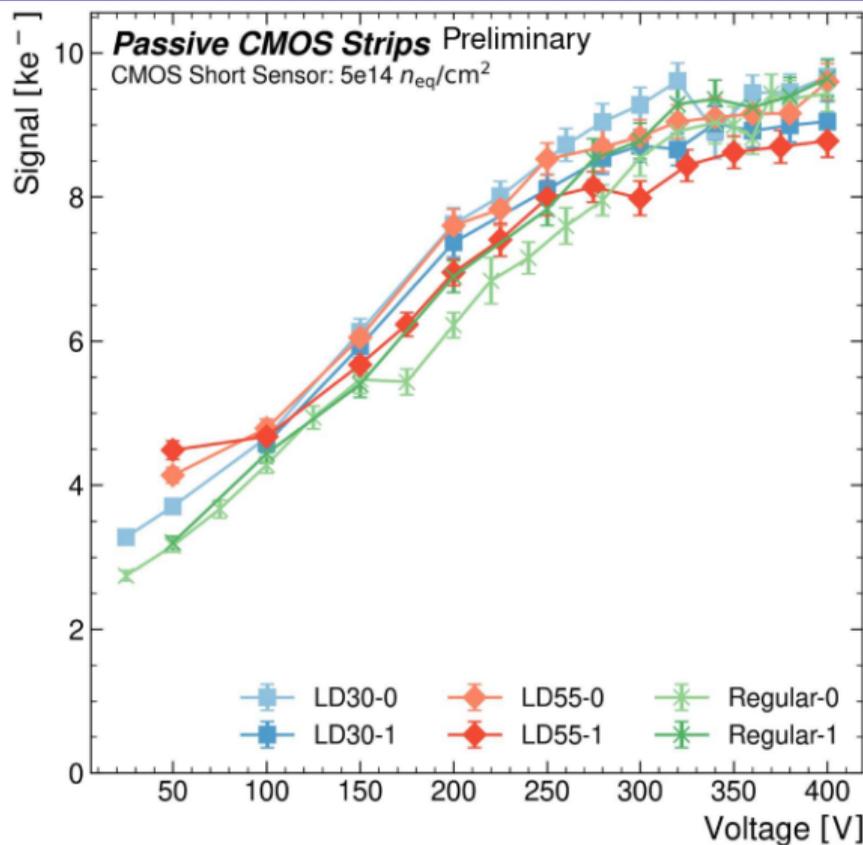
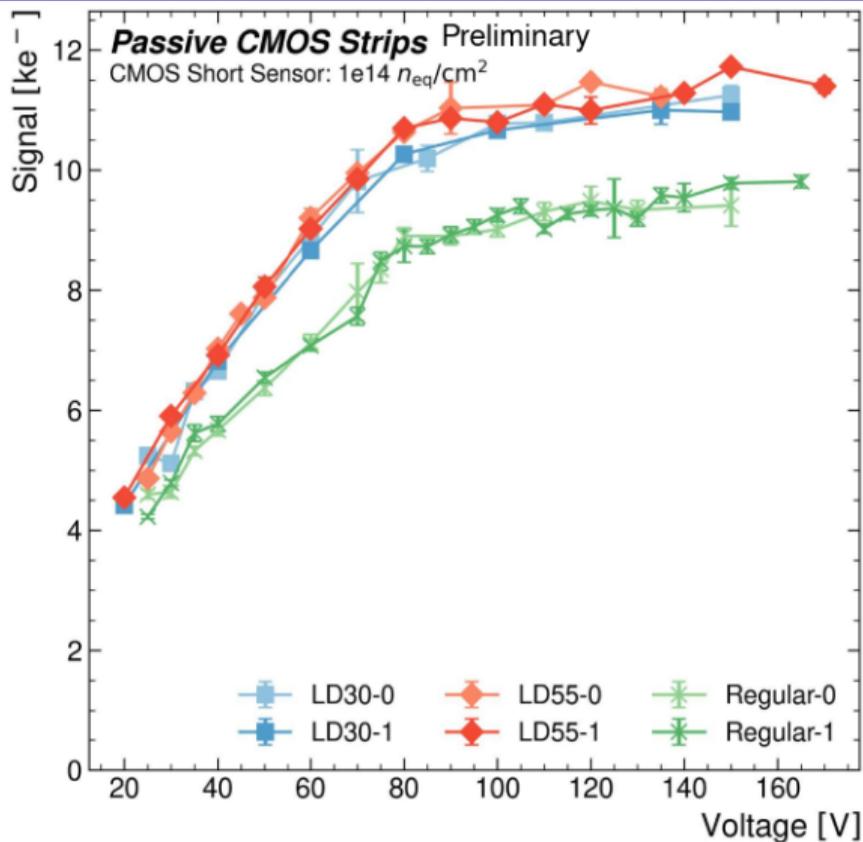
charge collection - unirradiated

- collimated ^{90}Sr β -decay source
- MIP-like e^-
- placed in front of different design and stitch regions

- regular and low dose 30 reach expected charge of $\sim 11.5 \text{ ke}^-$
- low dose 55 systematically low charge \rightarrow highest capacitance, maybe read-out electronics unable to handle it
- no stitching effect



charge collection - irradiated



Conclusion

- no effects of stitching detected
- promising radiation hardness
- BUT still ongoing investigation: more sensors, more fluences

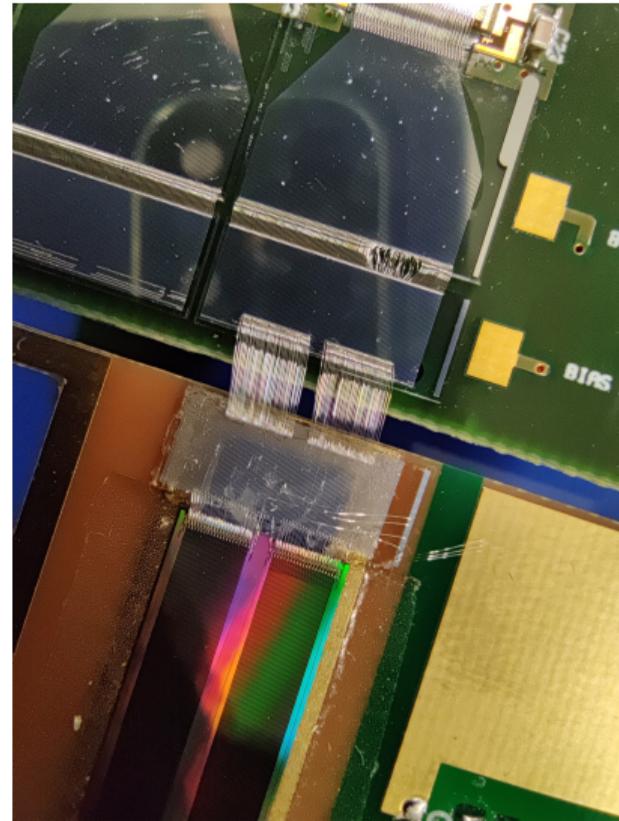
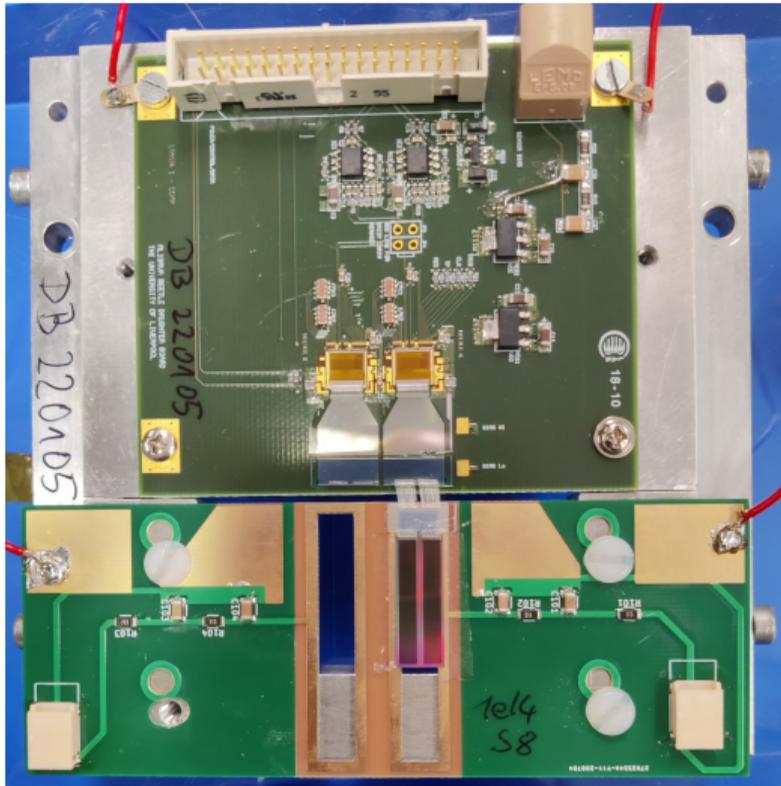
- larger areas, more strips
- fully utilise CMOS process and include electronics on substrate



Back-up

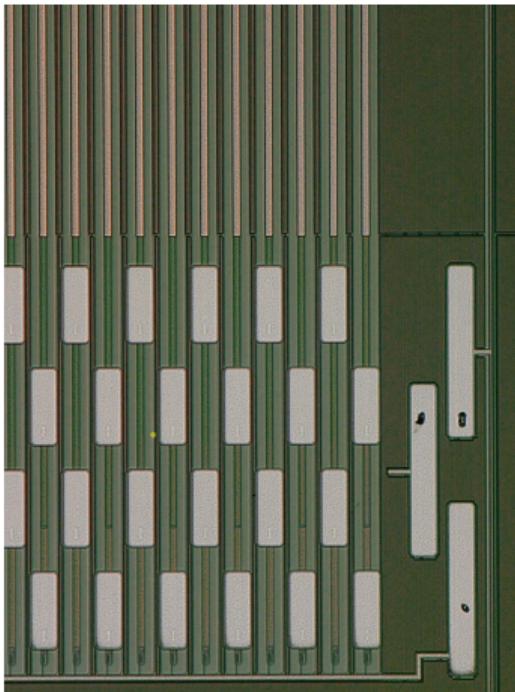


DB & Bonds

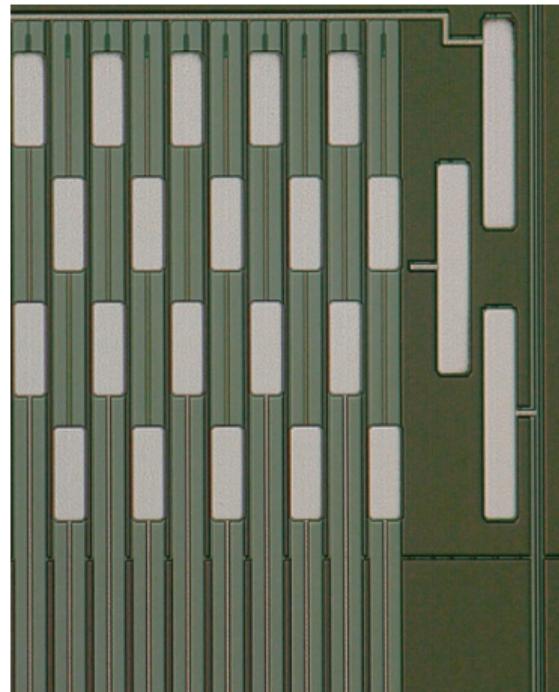


Sensor Design

regular

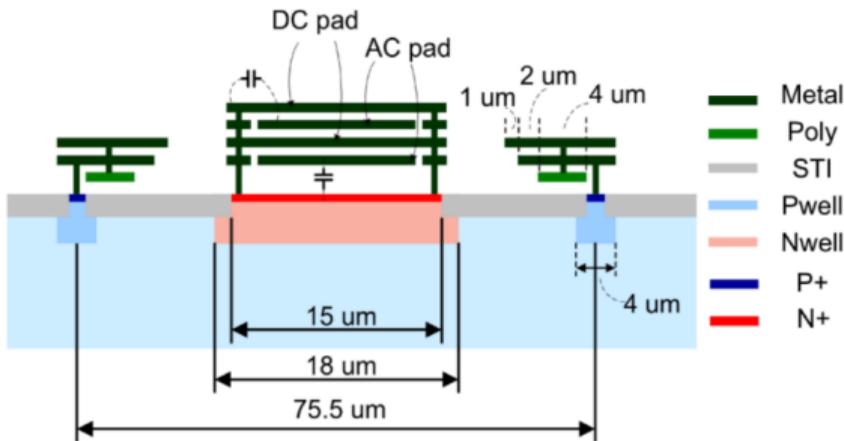


low dose 30/55

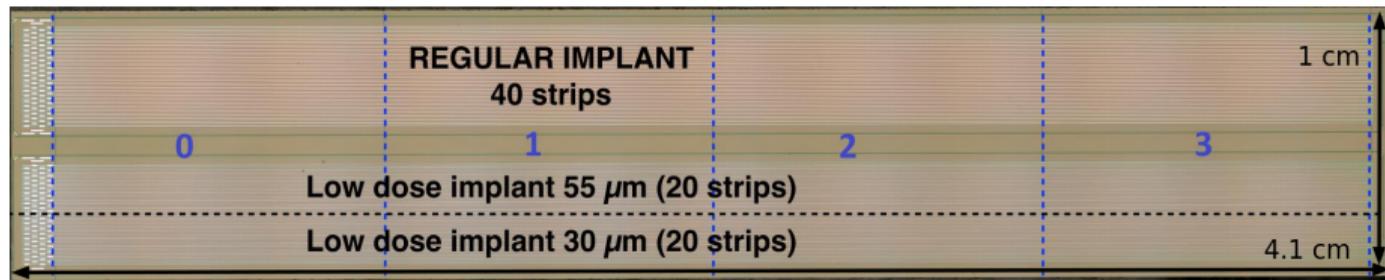
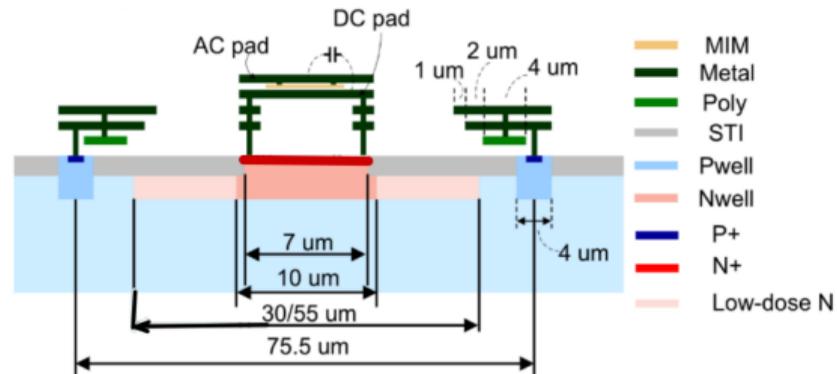


Sensor Design

regular design

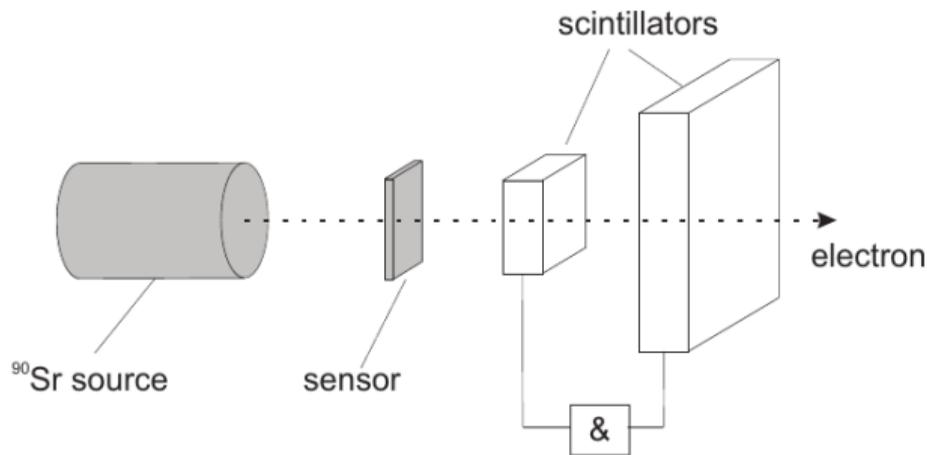


low dose 30/55 design



ALIBAVA setup

- ^{90}Sr β -decay source
 - collimated
 - gives MIP-like e^-
- two scintillators
 - trigger in coincidence
 - low energy cut
- sensor on daughterboard with beetle electronics



- inside freezer, additional liquid nitrogen cooling possible
- external motherboard for further signal processing and communication with software



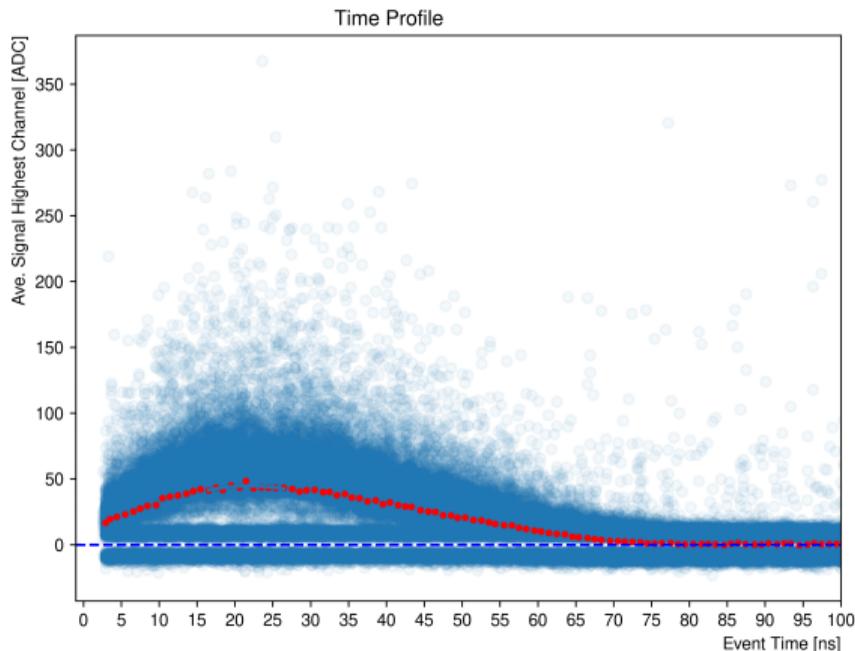
ALIBAVA measurement & analysis

- position source for different sensor design & stitch regions
- pedestal and source run
- motherboard 40 MHz signal sampling (LHC timing, 25 ns)
- TDC compares signal sample and trigger times
→ sort *snapshots* of signals acc. to time
- time cut: bias to smaller charge collected if too long
- seed & neighbour cut → cluster algorithm
- get collected charge from Landau-Gauss signal-fits



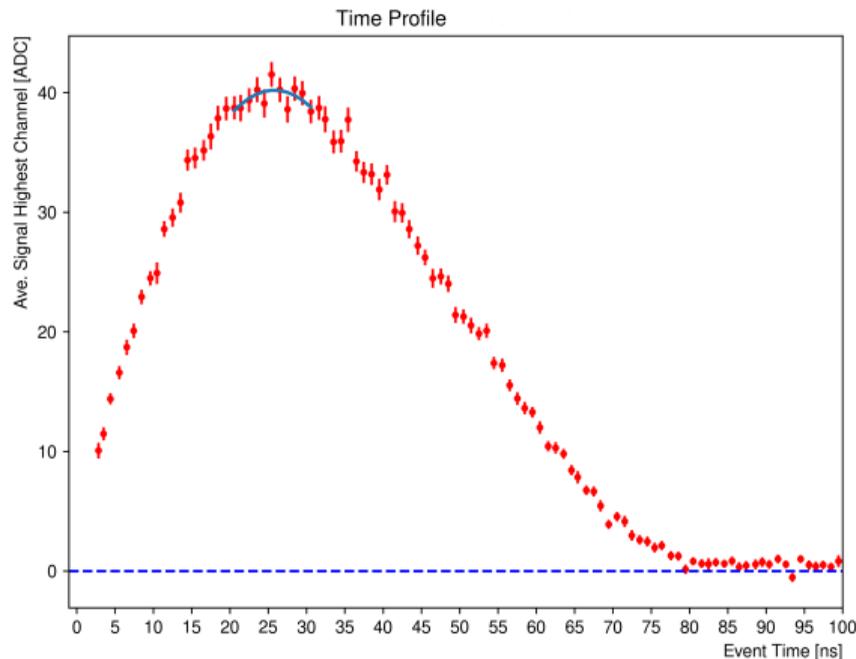
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500V, 10.6°C

